

| Ref # | Hits  | Search Query  | DBs  | Default Operator | Plurals | Time Stamp       |
|-------|-------|---|--|------------------|---------|------------------|
| L2    | 673   | ("xeF.sub.2" or "xenon difluoride") and vapor\$3 and etch\$3  | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR               | OFF     | 2005/12/12 10:28 |
| L3    | 328   | 2 and sacrificial   | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR               | OFF     | 2005/12/12 09:15 |
| L4    | 130   | ("xeF.sub.2" or "xenon difluoride") and vapor\$3 and etch\$3 and "flow rate"                          | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR               | OFF     | 2005/12/12 09:56 |
| L5    | 28325 | ("xeF.sub.2" or "xenon difluoride" or HF or hydrofluoric) and vapor\$3 and etch\$3                    | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR               | OFF     | 2005/12/12 10:29 |
| L6    | 4502  | ("xeF.sub.2" or "xenon difluoride" or HF or hydrofluoric) same vapor\$3 same etch\$3                  | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR               | OFF     | 2005/12/12 10:29 |
| L7    | 409   | ("xeF.sub.2" or "xenon difluoride" or HF or hydrofluoric) same vapor\$3 same etch\$3 same sacrificial | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR               | OFF     | 2005/12/12 11:07 |
| L8    | 355   | ("xeF.sub.2" or "xenon difluoride" or HF or hydrofluoric) same vapor\$3 same "flow rate"              | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR               | OFF     | 2005/12/12 11:07 |